

WHAT IS CLAIMED IS:

1. A substrate structure, comprising:
 - a substrate;
 - a plurality of thin film layers laminated on the substrate; and
 - a bank enclosing an area in which the plurality of thin film layers are arranged, the bank including a first layer, a second layer and a third layer, the second layer being disposed between the first and third layers, the first and third layers being made from one of an inorganic material and an organic material, the third layer being made from the other of the inorganic material and the organic material.
2. The substrate according to claim 1, the bank comprising alternately an affinity bank layer having affinity for the thin film layers and a non-affinity bank layer having non-affinity for the thin film layers.
3. The substrate according to claim 2, at least one of the affinity bank layer and the non-affinity bank layer being surface-treated so as to have affinity or non-affinity, respectively.
4. The substrate according to claim 2, the affinity bank layer including an inorganic material, and the non-affinity bank layer including an organic material.
5. The substrate according to claim 4, the organic material including an organic compound containing polyimide, amorphous silicon, polysilicon or fluorine, or an insulating organic compound.
6. The substrate according to claim 4, the inorganic material including A1, Ta, silicon oxide or silicon nitride.
7. The substrate according to claim 2, a thickness of the first thin layer being set to be the substantially the same thickness as the affinity bank layer at the lowest layer of the bank.

8. The substrate according to claim 7, a thickness of each thin film layer which is layered on the first thin film being set to be substantially the same thickness as the respective total thickness of the affinity bank layer and the non-affinity bank layer which are layered to the height corresponding to the bank.

9. The substrate according claim 8, the thickness of the non-affinity bank layer at the top layer being set to be 500 nm or less, and the thickness of the other non-affinity bank layer being set to be 100 nm or less.

10. The substrate according to claim 1, the thin film layers including an organic semiconductor.

11. The substrate according to claim 1, the thin film layers including a color filter.